

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:	§	
Chii-Ming WU, et al.	§	Confirmation No. 9336
	§	
Serial No.: 10/657,505	§	Group Art Unit: 2812
	§	
Filed: September 8, 2003	§	Examiner: Geyer, Scott B.
	§	
For: Method of Manufacturing a Contact	§	Attorney Docket No.:
Interconnection Layer Containing a Metal and	§	TS01-1247 / 24061.406
Nitrogen by Atomic Layer Deposition for	§	
Deep Sub-Micron Semiconductor	§	
Technology	§	

Commissioner for Patents
Mail Stop Amendment
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT

Sir:

The Commissioner is hereby authorized to charge Haynes and Boone, LLP's Deposit Account No. 08-1394. in the amount of \$120 for one-month extension of time for consideration of the present paper. If any other fees are necessary, including additional extension of time fees, the extension of time is hereby requested and the Commissioner is hereby authorized to charge any fees to Haynes and Boone, LLP's Deposit Account No. 08-1394.

In response to the Office Action of September 27, 2006, please amend the above-identified application as follows:

Listing of Claims are reflected in the listing of claims which begins on **page 2** of this paper.

Remarks begin on **page 9** of this paper.